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(54) Title: A NEGATIVE TONE LIFT OFF RESIST COMPOSITION COMPRISING AN ALKALI SOLUBLE RESIN AND A PHOTO ACID GENERATOR, AND A METHOD FOR MANUFACTURING METAL FILM PATTERNS ON A SUBSTRATE.

(57) Abstract: An object is to provide a resist composition which can form fine resist patterns and keep them. Another object is to provide a resist layer with good sensitivity and/or resolution. And another object is to provide a negative tone lift off resist composition that removability of resist patterns made from the composition is good. [Solution] The present invention provides a negative tone lift off resist composition comprising an alkali soluble resin and a photo acid generator. And the present invention provides a method for manufacturing metal film patterns on a substrate. The present invention provides a method for a manufacturing a device comprising metal film patterns manufacturing method.



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